

**Notice of References Cited**

Application/Control No.

09/681,894

Applicant(s)/Patent Under

 Reexamination  
DEVINE ET AL.

Examiner

W. David Coleman

Art Unit

2823

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,328,801	12-2001	Gary et al.	118/688
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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	N					
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	I.C. Kizilyalli et al., "Deuterium Post-Metal Annealing of MOSFET's for Improved Hot Carrier Reliability", IEEE Electron Device Letters, vol. 18, No. 3, March 1997, pp. 81-83
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	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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